§10. In-situ Optical Measurements of Decrystallization Induced by Ion Bombardment on Er<sub>2</sub>O<sub>3</sub>

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i) Introduction Optical methods are potentially useful for characterization of radiation-induced defects in ceramics blanket materials. Feasibility studies of the optical methods are undertaken for *in-situ* characterization of the radiation-induced defects in  $\text{Er}_2O_3$  by ion bombardment. The characterization is important for qualification of  $\text{Er}_2O_3$  coatings as electric insulation of Li/V-alloy blanket systems and as hydrogen permeation barriers.

A potentially useful luminescence band in 640-690 nm is identified as  $4f^{11} {}^{4}F_{9/2} - {}^{4}I_{15/2}$  transition of  $Er^{3+}$  at  $C_{2}$  cation sites. It has been demonstrated that ion bombardment on a plasma splay coating sample <sup>1</sup>) and a sintered bulk sample <sup>2</sup>) quenches preferentially the luminescence band.

ii) Modeling of luminescence quenching due to decrystallization by  $\mathbf{Ar}^+$  ion bombardment For a given local displacement per ion ( $\Phi$ ), a displacement per atom (dpa: C) at a depth (x) and an ion fluence (f) is written as,

$$C(x;f) = \frac{1}{Y} \int_0^\gamma \Phi(x - \gamma') d\gamma' \quad (x \ge \gamma), \qquad (1)$$

where  $\gamma = f \times Y/n$  is a surface erosion depth, and Y and n are a sputtering yield and an atomic number density of the target, respectively. Fractional number of emitters, *i. e.*  $\mathrm{Er}^{3+}$  cations, may be depopulated by an amount of  $\alpha \times C$ , where  $\alpha$  is a fraction of the dpa which contributes to depopulate the emitters. The depopulation of the emitting cations can be ascribed to decrystallization of the target. Figure 1 shows a measurement of luminescence quenching with  $\mathrm{Ar}^+$  (33 keV) ion fluences and fitting curves using the dpa given by Eq. 1. The local displacement per ion for  $\mathrm{Er}_2\mathrm{O}_3$  was calculated by using the TRIM code. The fitting is significantly sensitive to sputtering yield data used in the dpa calculation.

iii) Luminescence quenching by  $\mathbf{H}^+$  ion bombardment Figure 2 shows ion-induced luminescence spectra and its quenching with  $\mathbf{H}^+$  (34 keV) ion fluences. Intensity of the luminescence band at 640 – 690 nm preferentially decreases as the ion fluence increases. The relative intensity decreases rapidly until the ion fluence attains to  $2 \times 10^{21} / \mathrm{m}^2$ . At larger ion fluences, however, the relative intensity appears to have a finite value independent on the ion fluence. During the  $\mathbf{H}^+$  ion bombardment, not only decrystallization but also recovery may take place in the target at a finite temperature. In steady states, the luminescence intensity reaches at a value determined by rates of displacements and recombinations which may depend on temperature, projectile ion species and kinetic energies. This issue will be addressed in future studies.

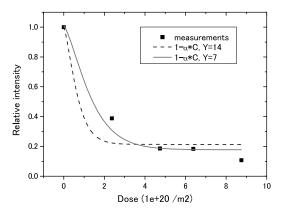


Fig. 1: Luminescence quenching with  $Ar^+$  (33 keV) ion fluences on a sintered  $Er_2O_3$  sample <sup>3)</sup>.

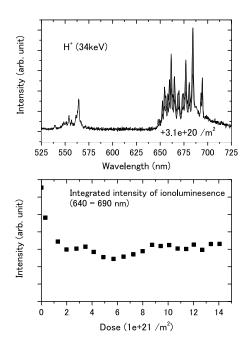


Fig. 2: Ion-induced luminescence spectra and its quenching with  $H^+$  (34 keV) ion fluences on a sintered  $Er_2O_3$  sample <sup>4)</sup>.

- 1) T. Tanaka et al., J. Nucl. Mater. (2011) vol.417 794.
- D. Kato *et al.*, Plasma Fusion Res. (2012) vol.7 2405043.
- D. Kato *et al.*, presented at the 9th joint meeting on Nucl. Fusion Energy, Jun. 28-29, 2012, Kobe, Japan.
- 4) D. Kato *et al.*, presented at the 29th JSPF annual meeting, Nov. 27-30, 2012, Kasuga, Japan.